

technical datasheet

AZ[®] P4K-AP Protective Coating

APPLICATION

Wafer surface protection during physical or chemical related processes.

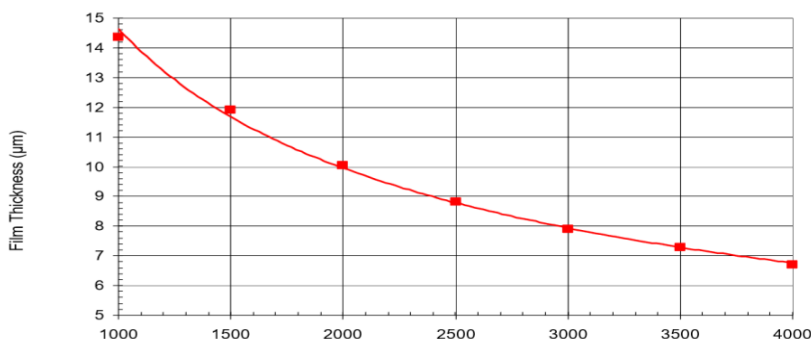
PRODUCTS AND FEATURES

AZ P4K-AP is a blend of resin and solvent components typical of fully formulated photoresists. The AZ P4K-AP Protective Coating excludes the photoactive component of a fully formulated photoresist, thus removing material and QA related costs for applications where photolithographic performance is unnecessary.

- The P4K-AP uses the same base materials as the industry standard AZ P4620 photoresist. It offers:
 - Superior adhesion to a wide variety of substrates
 - Compatible with many wet chemistries, both etch and plating
 - Good coating properties
 - Standard photoresist coating processes are used
- The P4K-AP can be used in:
 - Dry etch processes
 - Wet etch processes
 - Plating processes
- The P4K-AP is removed/stripped in standard wet or dry photoresist removal processes.

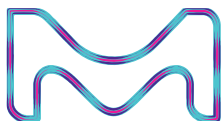
AZ[®] P4K-AP Protecting Coating

Spin Curve



Substrate: 150 mm Silicon
Spin Time: 30 seconds
Softbake: 110°C/ 180 sec hotplate

Spin Speed (rpm)



AZ[®] P4K-AP Protective Coating

EMD Part Number

21221223159, HDPE Gallon Bottle

MATERIALS COMPATIBILITY

AZ high purity solvents are compatible with all commercially available wafer and photomask processing equipment. Recommended materials of construction include PTFE, HDPE, stainless steel, polypropylene, and PFA. Recommended filtration media is PTFE.

STORAGE

Store AZ high purity solvents in sealed original containers located in a well ventilated, cool, dry environment away from sunlight, sparks, and open flames. Do not expose to excessive temperatures or moisture. Recommended storage temperature is >0°C. Empty containers may retain harmful residues.

Avoid contact with strong acids, alkaline materials, and oxidizing agents.

HANDLING PRECAUTIONS/FIRST AID

Avoid contact with skin and inhalation of vapors. **Always refer to the current version of the specific product MSDS for detailed information prior to handling.**

DISPOSAL

AZ high purity solvents are compatible with typical facility solvent drain lines and materials. For disposal other than via facility solvent drains, refer to the current product MSDS and to local regulations.

North America:

EMD Performance Materials
70 Meister Avenue
Somerville, NJ USA 08876
(908) 429-3500

Germany:

Merck Performance Materials
(Germany) GmbH
Wiesbaden, Germany
+49 611 962 4031

Korea:

Merck Performance Materials
(Korea) Ltd.
Seoul, Korea
+82 2 2056 1316

Singapore:

Merck Performance Materials
Pte. Ltd.
Jurong East, Singapore
+65 68900629

Taiwan:

Merck Performance Materials
Co. Ltd.
Hsinchu, Taiwan
+886 3 5970885#375

Japan:

Merck Performance Materials
G. K.
Tokyo, Japan
+81 3 5453 5062

China:

Merck Electronic Materials
Shanghai, China
+86 (21) 2083 2362

www.emd-performance-materials.com

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